

PCS 605 PHOTOMASK CLEANING SOLUTION

DESCRIPTION

Transene PCS 605 Photomask Cleaning Solution is a non-hazardous water-miscible cleaner for critical photomask cleaning applications. PCS 605 Photomask Cleaning Solution may be used on a variety of delicate mask substrates including iron oxide, chrome, or emulsion without damaging the surface. For emulsion masks, use at 1/8 dilution.

PROPERTIES

<u>Appearance</u>	<u>Colorless liquid</u>
<u>System</u>	<u>Non-Toxic Alkaline</u>
<u>Viscosity (RT)</u>	<u>10-30 cps</u>
<u>Specific Gravity</u>	<u>1.01</u>
<u>Shelf Life</u>	<u>6 months</u>
<u>Storage</u>	<u>Ambient</u>
<u>Filtration</u>	<u>0.1 μm</u>

APPLICATION:

Prior to further processing, the photomask should be submerged in PCS 605 Photomask Cleaning Solution. Cleaning is enhanced by ultrasonic or megasonic agitation. Alternatively, manual scrubbing is effective. Care should be taken not to damage the part while scrubbing gently. It is recommended that a clean room foam wipe be used to maximize the cleaning effect of the solution.

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